

## ABSTRACT

A positive resist composition, comprising a resin component (A) that exhibits increased alkali solubility under the action of acid, and an acid generator component (B) that generates acid on exposure, wherein the component (A) includes either a

5 silsesquioxane resin (A1) containing structural units (a1) represented by a general formula (I) shown below, structural units (a2) represented by a general formula (II) shown below, and structural units (a3) represented by a general formula (III) shown below, or a silsesquioxane resin (A2) containing structural units (a1) represented by the general formula (I) shown below, and structural units (a2') represented by a general formula (II') shown below. In the general formulas below,  $R^1$  represents a straight-chain or branched

10 alkylene group of 1 to 5 carbon atoms,  $R^2$  represents a straight-chain or branched alkylene group of 1 to 5 carbon atoms,  $R^3$  represents an acid dissociable, dissolution inhibiting group,  $R^6$  represents an alkyl group of 1 to 5 carbon atoms,  $R^7$  represents either an alkyl group of 1 to 5 carbon atoms or a hydrogen atom, and  $R^8$  represents an alicyclic

15 hydrocarbon group of 5 to 15 carbon atoms.



